Heeschen

NATIONAL RADIO ASTRONOMY OBSERVATORY Charlottesville, Virginia August 3, 1971

MEMORANDUM

| то: | Interferometer Group | | |
|----------|-----------------------|---------------|-----------|
| FROM: | M. C. H. Wright | | |
| SUBJECT: | H-Line Interferometer | - Calibration | Procedure |

Contents

- i) Calibration of the Interferometer Baseline
- ii) Calibration of the instrumental phase as a function of the observing frequency
- iii) Calibration of the IF pass-band
- iv) Frequency switching to remove the IF pass-band with high precision on strong absorption sources

Introduction

The reduction procedure is similar to that used for an interferometer at a fixed observing frequency. The basic equation for calibration is:

> > $-\phi$ calculated (assumed position and baseline)

+φ instrument (changes in instrument and atmosphere)

For a line interferometer the phase ϕ is a function of frequency and some additional calibrations must be made. The following is a suggested procedure for carrying these out.

1) Interferometer Baseline

This calibration must also be made for an interferometer observing at a fixed frequency. The procedure is to observe calibrating sources (unresolved sources at known positions) over a range of HA and DEC which cover the positions of the sources being investigated. Assuming that the sources are unresolved and that the correct positions (r)have been given, the observed phase is then the sum of phase due to errors in the assumed baseline plus the instrumental phase.

Thus ϕ observed = $\mathbf{r} \cdot \Delta \mathbf{B} + \phi_0$

If the calibrating sources are observed at the same <u>frequency</u> (not velocity) then a least squares solution can be made to obtain a correction for the assumed baseline and the residual phase ϕ_0 is the instrumental phase which is a function of time and can be directly edited out of the data.

If the calibrating sources are observed over a range of observing frequencies, then the instrumental phase, ϕ_0 , will be a function of frequency due to unequal cable lengths at the variable synthesis frequency, and a solution must be made to include this effect. (Clearly a better solution will be obtained if attempts are made to observe the calibrating sources within a short period of time when the instrumental phase is relatively stable and over a small range of frequencies.)

2. Instrumental Phase

Just as the determinations of the baseline is confused by the frequency dependence of the instrumental phase, the reverse is also true. Although a combined least squares solution may be made for baseline and frequency dependence a better solution will be obtained if a single source is observed in a short time over a wide range of frequencies.

Both of these calibrations are made independent of the frequency channel and either the broad band continuum channels or the added frequency channels should be made to obtain the greatest signalto-noise ratio. Several passes through the data may be made to find a solution interatively,

- i) correcting for the frequency dependence if a separate calibration has been made
- ii) correcting for baseline errors
- iii) editing the time dependence of the instrumental phase
- iv) re-cycling as desired

3. Passband Correction

In addition to the frequency channel independent calibrations above, correction for the shape of the IF passband of the cross correlator may also be made.

The passband is determined as the shape of the spectrum resulting from the observation of a source without frequency structure. This passband shape may then be removed from other data. The same calibrators as were used to calibrate the baseline and instrumental phase may be used to determine the passband and this will be the best procedure for calibrating weak sources. However for strong sources the passband may be determined with greater precision by observing the same source off-frequency (i.e., at a frequency where it lacks frequency dependent structure). Calibration of strong absorption sources is discussed in section 4.

The IF passband correction is most clearly presented mathe-The amplitude and phase response in frequency channel i: matically.

i) On source - on frequency

 $= A_{i}(k) e^{j\phi(k)} \times b_{i} e^{j\xi_{i}} \times e^{j\eta}$

structure of source (k) IF passband instrumental k = spactial frequency

phase + baseline (1)

ii) Calibrator - on frequency

-unresolved, ... constant amplitude

If there is no trouble from local absorption in the calibrator, then after correcting the baseline $\eta = \eta^1$ and <u>dividing</u> (1) by (2) gives us the source structure directly in units of the calibrator flux.

iii) If local absorption in the calibrator is a problem then the calibrator may be observed off frequency to give

$$a \times b_{i} e^{j\xi_{i}} \times e^{j\eta^{1}} + e^{j\Delta\eta}$$
(3)

frequency dependence of instrumental phase

We must now correct for baseline and phase-frequency dependence before dividing.

4. Strong Absorption Sources

The passband correction is limited by the noise in the individual frequency channels and for a strong source the calibration is best obtained from an <u>on-source</u>, <u>off-frequency</u> observation. In the case of finding the structure of the absorbing material this also eliminates the need to find the interferometer baseline.

The response in frequency channel i is:

i) <u>On source - on frequency</u>

=
$$A(k) e^{j\phi(k)} x e^{\tau_i(k)} e^{j\Psi_i(k)} x b_i e^{j\xi_i} x e^{j\eta}$$
 (4)
source structure absorption & IR instrumental
independent of frequency struc- passband phase

- frequency ture
- ii) <u>On source off frequency</u>

$$A(k) e^{j\phi(k)} \times b_i e^{j\xi_i} \times e^{j(n + \Delta n)}$$
(5)

frequency dependence of instrumental phase

Dividing (4) by (5) gives:

 $e^{\tau_i(k)} e^{j\Psi_i(k)} x e^{-j\Delta \eta}$

and we need only correct for the phase-frequency dependence to obtain the absorption structure directly.

The source structure may be obtained separately from the continuum or added channels of the off-frequency observation and a baseline determination is then required.